

AMENDMENTS TO THE SPECIFICATION

Please replace the paragraph beginning at page 24, line 21, which starts with "When the gas . . ." with the following amended paragraph.

When the gas containing no CF_4 gas, i.e., the gas containing no halogen atom, was caused to contain N_2 gas, the intensity ratio A/B did not attain a maximum value, thereby failing to yield a value exceeding the intensity ratio A/B caused by the emission of a plasma which was 100% oxygen as can be seen from FIG. 6. When the gas containing CF_4 gas was caused to contain N_2 gas, by contrast, a maximum value was obtained at an appropriate value. These facts have revealed that desirable etching in this embodiment cannot be realized when N_2 gas is simply added to O_2 gas, but a diamond product having a substantially perpendicular side face and a flat etching face can be obtained when N_2 gas is added to a mixed gas containing O_2 gas and $[\text{N}_2]$ CF_4 gas.